

Method for Cleaning Lithium-Niobate Single-sided Polished Wafer

Abstract

Provided is a method for cleaning lithium-niobate single-sided polished wafer, wherein the method comprises soaking the lithium niobate wafer in ammonium hydrogen fluoride for cleaning; subjecting the wafer to ultrasonic cleaning with an organic solvent cleaning solution; rinsing the wafer with deionized water; performing brushing by dual-sided brush on the wafer; and conducting brushing by single-sided brush on the wafer. In the end, this method results in a lithium niobate wafer with low fragment rate and high cleanliness.